AMENDMENTS TO THE SPECIFICATION

Page 42

Please amend the paragraph beginning on line 3 through Page 43, line 6 as follows:

After the above-mentioned substantially circular images are selected, the photomicrograph is subjected to mapping with respect to the images of pores therein, to thereby count the number of pores and calculate the pore opening area of each of the pores. The total of pore opening areas of all pores in the photomicrograph is designated as (S), the total of pore opening areas of pores (P) each having a pore opening area larger than (a_2) is designated as (S_{a2}), the total of pore opening areas of pores each having a pore opening area larger than ($a_2 + \sigma$) is designated as ($S_{(a2+\sigma)}$), the total of pore opening areas of pores each having a pore opening area larger than ($a_2 + 2\sigma$) is designated as ($S_{(a2+2\sigma)}$), and the total of pore opening areas of pores each having a pore opening area larger than ($a_2 + 3\sigma$) is designated as ($S_{(a2+3\sigma)}$). In the present invention, with respect to the porous silica layer, it is preferred that (S_{a2}) and (S) as described above satisfy the formula: $(S_{a2})/(S) \geq 0.5$; it is more preferred that ($S_{(a2+\sigma)}$) and (S) as described above satisfy the formula: $(S_{(a2+\sigma)})/(S) \geq 0.5$; it is still more preferred that ($S_{(a2+2\sigma)}$) <u>and (S)</u> as described above ~~satisfies~~ <u>satisfy</u> the formula ~~$(S_{(a2+2\sigma)}) \geq 0.5$~~ <u>$(S_{(a2+2\sigma)})/(S) \geq 0.5$</u>; and it is still more preferred that ($S_{(a2+3\sigma)}$)<u> and (S)</u> as described above ~~satisfies~~ <u>satisfy</u> the formula: ~~$(S_{(a2+3\sigma)}) \geq 0.5$~~ <u>$(S_{(a2+3\sigma)})/(S) \geq 0.5$</u>. When $(S_{a2})/(S)$ is less than 0.5, there is a possibility that the refractive index of the porous silica layer becomes disadvantageously as high as 1.30 or more, thus rendering unsatisfactory the antireflection effect of the porous silica layer.

Page 78

Please amend the paragraph beginning on line 11 through Page 79, line 11 as follows:

Substantially the same procedure as in Example 1 was repeated except that the commercially available hard coat layer~~-~~forming agent (trade name: UVHC1101; manufactured and sold by GE Toshiba Silicones Co., Ltd., Japan) was replaced by another product of hard coat layer~~-~~forming agent (trade name: KAYANOVA FOP-1100; manufactured and sold by Nippon Kayaku Co., Ltd., Japan), and that the coating (of the hard coat layer~~-~~forming agent) formed on the PET film was subjected to heating at 120 °C for 1 minute using a forced convection oven, and then cured by irradiating ultraviolet rays for 360 seconds using a photo surface processor (trade name: PL16-110; manufactured and sold by Sen Engineering Co., Ltd., Japan) (illumination intensity at a wavelength of 250 nm: 13 mW/cm^2), thereby forming a hard coat layer having a thickness of 8 μm. The hard coat layer of the obtained transparent substrate had a water contact angle of 47 ° and a pencil hardness of 2H. The coating composition was able to be coated on the entire surface of the transparent substrate, i.e., the coating formability of the coating composition is good. Various properties of the obtained laminated structure are shown in Table 1 and Table 3. The laminated structure exhibited a minimum reflectance of 0.10 % at a wavelength of 550 nm. The pencil hardness was 2H, which is good. The refractive index n of the porous silica layer was 1.26. The haze was 0.5 %, which is good.